

FPA-3030i5a i-line Stepper for Power, 5G & IoT Applications

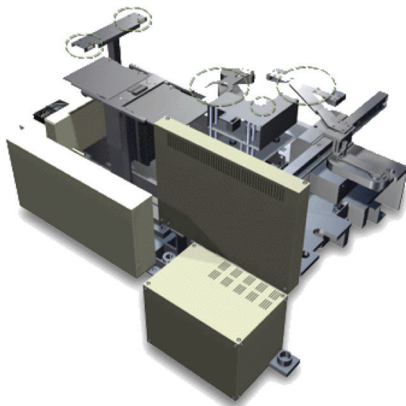


FPA-3030i5a FEATURES

- Resolution ≤ 350 nm
- Lens Reduction 5:1
- Substrate handling capability: 50, 75, 100, 150, 200 mm
- FPA-3030i5a Steppers leverage and extend proven Canon FPA-3000 Stepper designs
- Canon Built-In Metrology (CANOMAP)

KEY OPTIONS

- Through Silicon Alignment (TSA) Scope
- Die-by-Die Overlay Compensation (EAGA)
- Multi-Wafer Size Handling Kit
 - 75 & 100 mm, 100 & 150 mm, 150 & 200 mm
- Warped/Bonded/Transparent Wafer Handling
- Pellicle Particle Checker
- PC Remote Console
- GEM-compliant online software



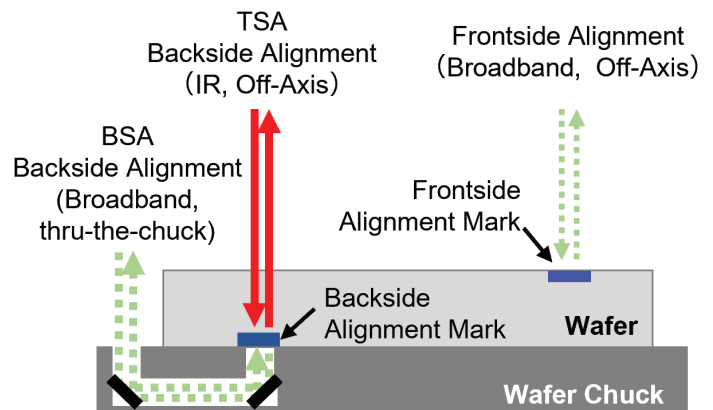
Multi-Wafer Size Handling Kits allow quick changeover between two wafer sizes
75 ↔ 100 mm, 100 ↔ 150 mm, 150 ↔ 200 mm

High-Resolution i-line Stepper for ≤ 200 mm Wafer Fabrication

FPA-3030i5a [30i5+] Steppers deliver performance and flexibility required for manufacturing and R&D environments and support a variety of substrates including GaAs, GaN and transparent sapphire and SiC wafers.

The 30i5a is able to support a range of wafer sizes for innovative Internet-of-Things (IoT), 5G, automotive, power and Micro-electromechanical Systems (MEMS) applications and can be configured to process wafers from 50 mm (2") to 200 mm (8") in diameter. 30i5a systems can also be configured to handle two different wafer sizes with the Multi-Wafer Handling Kit option.

The resolution, overlay, productivity and available options of the 30i5a make it a cost-effective solution for challenging ≤ 200 mm wafer processes.



FPA-3030 Stepper Backside Alignment Options enable front-to-back overlay alignment

SPECIFICATIONS

| | |
|------------------------|---|
| Technology | i-line Stepper (365 nm) |
| Resolution | ≤ 350 nm |
| Overlay | ≤ 40 nm (Front) ≤ 150 nm (Front, TSA)* |
| Numerical Aperture | 0.45 – 0.63 |
| Lens Reduction Ratio | 5:1 |
| Exposure Field | 22 x 22 mm |
| Substrate Size Options | 50, 75, 100, 125, 150, 200 mm |
| Dimensions (W x D x H) | 1.9 x 2.6 x 2.45 m |

* = Option Required

Canon Lithography Systems

Canon Photolithography equipment is designed to help provide exceptional quality, performance, and cost of ownership for your wafer imaging applications.

Canon FPA (Fine Pattern Aligner) Series Nanoimprint, i-line and Deep Ultraviolet (DUV) lithography systems are used in the fabrication and heterogeneous integration of high-tech devices including integrated circuits, hard disk read/write heads, microelectromechanical systems (MEMS) devices, image sensors, displays, power devices and light emitting diodes (LED).

LITHOGRAPHY PRODUCTS & TARGET APPLICATIONS

| Lithography Products | Technology | Resolution | Lens Red. Field Size [mm] | Substrate Options [mm] | MRAM | Logic & MPU/GPU | Medical | HDD & SCM | Power & Automotive | Waveguide & RF | Advanced Packaging | Optics & Photonics | MEMS, Sensors & IoT | PC & Mobile | 5G & Data Centers | Wearables | AR/VR & Display | LED, MicroLED | Artificial Intelligence |
|----------------------|-------------------------|------------------------------------|---------------------------|------------------------|------|-----------------|---------|-----------|--------------------|----------------|--------------------|--------------------|---------------------|-------------|-------------------|-----------|-----------------|---------------|-------------------------|
| FPA-1200NZ2C | Nanoimprint Lithography | ≤15 nm | 1:1 26 x 33 | 300 | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-8000iW | i-line (365 nm) Stepper | ≤ 0.8 μm | 2:1 55 x 55 | 510 x 515 | | | ✓ | | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-3030i5a | i-line (365 nm) Stepper | ≤ 350 nm | 5:1 22 x 22 | ≤ 200 | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | | ✓ | ✓ |
| FPA-3030iWa | i-line (365 nm) Stepper | ≤ 0.8 μm | 2:1 52 x 52 | ≤ 200 | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-3030EX6 | KrF (248 nm) Stepper | ≤ 150 nm | 5:1 22 x 22 | ≤ 200 | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | | ✓ | ✓ |
| FPA-5520iV LF2 | i-line (365 nm) Stepper | ≤ 0.8 μm | 2:1 54 x 68 | 300 | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-5550iZ2 | i-line (365 nm) Stepper | ≤ 350 nm ≤ 280 nm (2/3 Ann.) | 4:1 26 x 33 | 200 300 | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-5510iX | i-line (365 nm) Stepper | ≤ 0.5 μm | 2:1 50 x 50 | 300 | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |
| FPA-6300ES6a | KrF (248 nm) Scanner | ≤ 100 nm ≤ 90 nm (2/3 Ann.) | 4:1 26 x 33 | 200 300 | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | | ✓ |
| FPA-6300ESW | KrF (248 nm) Scanner | ≤ 130 nm | 3.125:1 33 x 42.2 | 200 300 | | | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | | ✓ |
| MS-001 | Overlay Metrology | --- | --- | 300 | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ | ✓ |

✓ Compatible with application

All options may not be available on all models. Contact Canon for details.



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